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Contents

- v *Authors*
- vii *Symposium Committees*
- xi *Conference Committee*

LASER MICRO/NANOFABRICATION AND ULTRAFAST LASER PROCESSING I

- 11183 05 **Investigation on UV solid-state nanosecond laser micromachining of microstructures on sapphire wafer [11183-4]**

LASER MICRO/NANOFABRICATION AND ULTRAFAST LASER PROCESSING II

- 11183 07 **Laser-induced backside wet/dry etching microstructures on transparent and brittle materials (Invited Paper) [11183-6]**
- 11183 09 **Laser-induced hierarchically-structured materials from block copolymer self-assembly [11183-10]**
- 11183 0A **Fabrication and testing of the smallest “flute” on syringe needles [11183-9]**

LASER MACRO PROCESSING

- 11183 0B **Fabrication of high strength and lightweight dissimilar material joints by laser: a review (Invited Paper) [11183-11]**
- 11183 0D **Numerical simulation of fiber laser cutting CFRP with different resin matrix contents [11183-13]**
- 11183 0F **Research on the effect of microtexturing pretreatment on laser welding of CFRTP and aluminum alloy [11183-15]**

LASER ADDITIVE MANUFACTURING AND LASER PEENING I

- 11183 0I **AlCrFeMnNi high-entropy alloy fabricated by laser additive manufacturing under direct-current electric field controlled [11183-18]**

POSTER SESSION

- 11183 OR **Research on picosecond laser processing technology of ceramic materials involving incident angle** [11183-8]
- 11183 OT **The anti-icing characteristics of micro/nano surface of stainless steel prepared by femtosecond laser** [11183-28]
- 11183 OU **Fast formation of hybrid periodic surface structures on Hf thin-film by focused femtosecond laser beam** [11183-29]
- 11183 OW **Laser and electrochemical hybrid machining (LECM) based on internal total reflection effect** [11183-31]
- 11183 OX **Simulation and experimental verification of water-guided laser processing by a water-gas shrinkage laminar flow method** [11183-32]
- 11183 OY **Effect of energy input on laser welded AISi10Mg parts fabricates by selective laser melting** [11183-33]

Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Babin, S. A., 0U
Belousov, D. A., 0U
Bronnikov, K. A., 0U
Cao, Qing, 0Y
Chang, Yaoqing, 0Y
Chen, Xiaoxiao, 0R
Cui, Li, 0Y
Dostovalov, A. V., 0U
E., Yiwen, 0A
Fan, A., 0D
Gao, Shenghan, 0A
Guo, Chunhai, 0X
He, Dingyong, 0Y
Huang, Hui, 0Y
Jia, Shaohui, 0F, 0I
Jiao, Junke, 0F, 0I
Jin, Zeqing, 0A
Korolkov, V. P., 0U
Li, J. G., 07
Li, M. N., 07
Lin, Jingquan, 0T
Liu, Y., 05
Liu, Ziyuan, 0T
Long, J. Y., 07
Ouyang, Wentai, 0F, 0I
Qi, L., 05, 0D
Shen, Zhikang, 0B
Tan, Caiwang, 0B
Tan, Kwan W., 09
Tao, Haiyan, 0T
Wang, Heng, 0R
Wang, Yufeng, 0W
Wu, Yaowen, 0X
Xiao, Rui, 0B
Xie, X. Z., 07
Xu, Zifa, 0F, 0I
Yang, Feng, 0W
Yang, Jin, 0B
Ye, Yiyun, 0F, 0I
Yu, Zhishui, 0B
Zeng, Yong, 0Y
Zhang, Guangyi, 0X
Zhang, Mina, 0F, 0I
Zhang, Mingchi, 0T
Zhang, Wenwu, 0F, 0I, 0R, 0W, 0X
Zhang, X.-C., 0A
Zhang, Zheng, 0X
Zhou, C. X., 07
Zou, Z. S., 07

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- 3 Laser Macro Processing
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- 4 Laser Additive Manufacturing and Laser Peening I
Yuji Sano, Institute for Molecular Science (Japan)
- 5 Laser Additive Manufacturing and Laser Peening II
Yuji Sano, Institute for Molecular Science (Japan)

